

**WHAT IS CLAIMED IS:**

1. A chemical vapor deposition apparatus comprising:  
a chamber having an inner space;  
a gas feed member for supplying a gas into the chamber;  
5 a susceptor disposed in the chamber and supporting a substrate;  
a diffuser partitioning the inner space of the chamber into first and second  
partitions and having a plurality of holes connecting the first partition and the second  
partition for gas communication; and  
an insulating frame disposed between the chamber and the diffuser,  
10 wherein the diffuser includes an extension overlapping a surface of the  
insulating frame.
2. The apparatus of claim 1, wherein the extension of the diffuser has an  
"L" shape.
3. The apparatus of claim 1, wherein the diffuser comprises Al or  
15 stainless steel.
4. The apparatus of claim 1, wherein the insulating frame comprises  
ceramic.
5. The apparatus of claim 1, wherein the substrate comprises glass.
6. The apparatus of claim 1, wherein the substrate is prepared for a  
20 liquid crystal display.
7. The apparatus of claim 1, further comprising a blocking member for  
mixing and spreading the gas from the gas feed member before the gas passes through  
the holes of the diffuser.
8. The apparatus of claim 1, wherein the diffuser is electrically powered  
25 and the susceptor is electrically grounded.
9. A chemical vapor deposition apparatus comprising:  
a chamber having an inner space;  
a gas feed member for supplying a gas into the chamber;  
a susceptor disposed in the chamber and supporting a substrate;  
30 a diffuser partitioning the inner space of the chamber into first and second  
partitions and having a plurality of holes connecting the first partition and the second  
partition for gas communication;

a diffuser frame incorporated into the diffuser; and  
an insulating frame disposed between the chamber and the diffuser.